

PATENT APPLICATION
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q80214

Tsutomu SHOKI, et al.

Appln. No.: 10/789,990

Group Art Unit: 1756

Confirmation No.: 9533

Examiner: Stephen D. Rosasco

Filed: March 2, 2004

For: REFLECTIVE MASK BLANK HAVING A PROGRAMMED DEFECT METHOD OF PRODUCING THE SAME, REFLECTIVE MASK HAVING A PROGRAMMED DEFECT AND METHOD OF PRODUCING THE SAME, AND SUBSTRATE FOR USE IN PRODUCING THE REFLECTIVE MASK BLANK OR THE REFLECTIVE MASK HAVING A PROG

AMENDMENT UNDER 37 C.F.R. § 1.111

MAIL STOP AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated September 19, 2006, please amend the above-identified application as follows on the accompanying pages.

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